

 SCANNED <u>KW</u> O.I.P.E. <u>2</u> Q.A. <u>IN</u>	PATENT DATE
---	-------------

APPLICATION NO. 09/617454	CONT/PRIOR	CLASS 134	SUBCLASS 001.1	ART UNIT 1746	EXAMINER SMITH MARKOFF MARKOFF
------------------------------	------------	--------------	-------------------	------------------	---

NTS Walter Branco
Jianmin Qiao

Method for cleaning plasma etch chamber structures

PTO-204
12/93

ISSUING CLASSIFICATION											
ORIGINAL				CROSS REFERENCE(S)							
CLASS		SUBCLASS		CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)						
INTERNATIONAL CLASSIFICATION											

☐ Continued on Issue Slip inside File Jacket

<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	_____ (Assistant Examiner) (Date)			NOTICE OF ALLOWANCE MAILED	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S. Patent. No. _____ _____ _____	_____ (Primary Examiner) (Date)			ISSUE FEE	
				Amount Due	Date Paid
<input type="checkbox"/> The terminal ____ months of this patent have been disclaimed.	_____ (Legal Instruments Examiner) (Date)			ISSUE BATCH NUMBER	
WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368.					

Form **PTO-436A**
(Rev. 6/99)

FILED WITH: ☐ DISK (CRF) ☐ FICHE ☐ CD-ROM
(Attached in pocket on right inside flap)

(FACE)